

Al Plasma Etch Recipe

Plasma-Therm SLR RIE

January 14, 2013

Equipment

Equipment	Plasma-Therm SLR RIE
Manufacture	Plasma-Therm
Model	unknown
Years in Service	10 years

Recipe

Recipe Name	STDAL.prc	
Gas	BCl ₃	40 sccm
	Cl ₂	10 sccm
Platen Power	125 W	
RF Frequency	13.56 Mhz	
Chamber Pressure	60 mTorr	
Platen Temperature	25 °C	

Results ^a

Etch Rate	A/min ^b
Uniformity	% ^c
Selectivity	

^a: An average value from monthly testing since Nov. 2012

^b: An average value from 15 min deposition

^c: Film thickness variation across a 4" wafer

^d: An average value across a 4" wafer

^e: Measured with optical stress measurement tool

^f: An average value from 15 min etch